

AMENDMENTS TO THE ABSTRACT:

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ABSTRACT

A lithographic interferometer system includes a beam generating mechanism, mirrors which reflect those beams, and detection devices configured to detect an interference pattern of overlapping reflected beams. The beam generating mechanism includes a beam-splitter, which splits the beams into reference beams and measuring beams, a reference mirror that provides a plane mirror interferometer, and a reflective surface that emits at least one reference beam used in a differential plane mirror interferometer.